



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

Wen-Ben CHOU et al.

Application No. 09/998,858

Filed: October 31, 2001

For: METHOD AND APPARATUS  
FOR NITRIDE SPACER ETCH  
PROCESS IMPLEMENTING -  
IN SITU INTERFEROMETRY  
ENDPOINT DETECTION AND  
NON-INTERFEROMETRY  
ENDPOINT MONITORING

Docket No. LAM2P295

Examiner: Chen, Kin Chan

Group Art Unit: 1765

Date: July 1, 2004

**CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450 on July 1, 2004.

Signed:

Courtney F. Yadegar

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Dear Sir:

This is in response to the Office Action mailed on April 1, 2004. Please enter the following amendments and remarks in the above-identified patent application:

Amendments to the claims are reflected in the Listing of Claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.

07/21/2004 RHOLLAND 00000004 500805 09998858

01 FC:1201 344.00 DA